CLAIM AMENDMENTS:

Claim 1 (Canceled).

Claim 2 (Currently amended): The combined semiconductor apparatus according to claim 5, wherein said planarized region is a part of said surface of said semiconductor silicon substrate which has been subjected to a planarizing process.

Claims 3 and 4 (Canceled).

Claim 5 (currently amended): A combined semiconductor apparatus, comprising:

a semiconductor silicon substrate having an integrated circuit formed therein, the silicon substrate having a rough or irregular surface due to at least a wiring pattern of the integrated circuit;

a planarized region defined over said rough or irregular surface of said silicon substrate;

a planarized film disposed over said planarized region; and
a semiconductor thin film disposed over said planarized film, the
semiconductor thin film including at least one semiconductor device a lightemitting element and being bonded on [[a]] said planarized film, so that said
semiconductor thin film is disposed above the integrated circuit and said

<u>circuit</u> region defined on a surface of said semiconductor substrate, wherein:

said semiconductor thin film is made of a compound semiconductor as a main material; and

a planarized film disposed between said planarized region and said semiconductor thin film, wherein a surface of said planarized film on a side of said semiconductor thin film has been subjected to a planarizing process.

Claim 6 (Currently amended): The combined semiconductor apparatus according to claim 5, wherein said planarized film includes:

an electrically conductive layer <u>contacting with said light-emitting</u> <u>element</u>; and

an interdielectric layer formed in a region peripheral to said electrically conductive layer.

Claims 7 and 8 (Canceled).

Claim 9 (Currently amended): The combined semiconductor apparatus according to claim 5, wherein said semiconductor thin film has a common electrode layer on a second surface of the semiconductor thin film opposed to a first surface of the semiconductor thin film, in which said semiconductor device light-emitting element is formed, and

said second surface of said semiconductor thin film is disposed on a side of said planarized region of said semiconductor silicon substrate.

Claim 10 (Currently amended): The combined semiconductor apparatus according to claim 9, wherein said integrated circuit includes individual electrode terminals; <u>and</u>

said apparatus further comprising individual interconnecting lines formed on a region extending from an upper surface of said semiconductor device light-emitting element to said individual electrode terminal.

Claims 11- 17 (Canceled).

Claim 18 (Currently amended): The combined semiconductor apparatus according to claim 5, wherein said at least one semiconductor device light-emitting element is a plurality of said semiconductor devices light-emitting elements arranged in said semiconductor thin film.

Claim 19 (Canceled).

Claim 20 (previously presented): An optical print head including the combined semiconductor apparatus of claim 5.

Claims 21-36 (Canceled).